

## **Supplementary Information: *Journal of Materials Chemistry***

### **High work function anode interfacial layer via mild temperature thermal decomposition of C<sub>60</sub>F<sub>36</sub> thin film on ITO**

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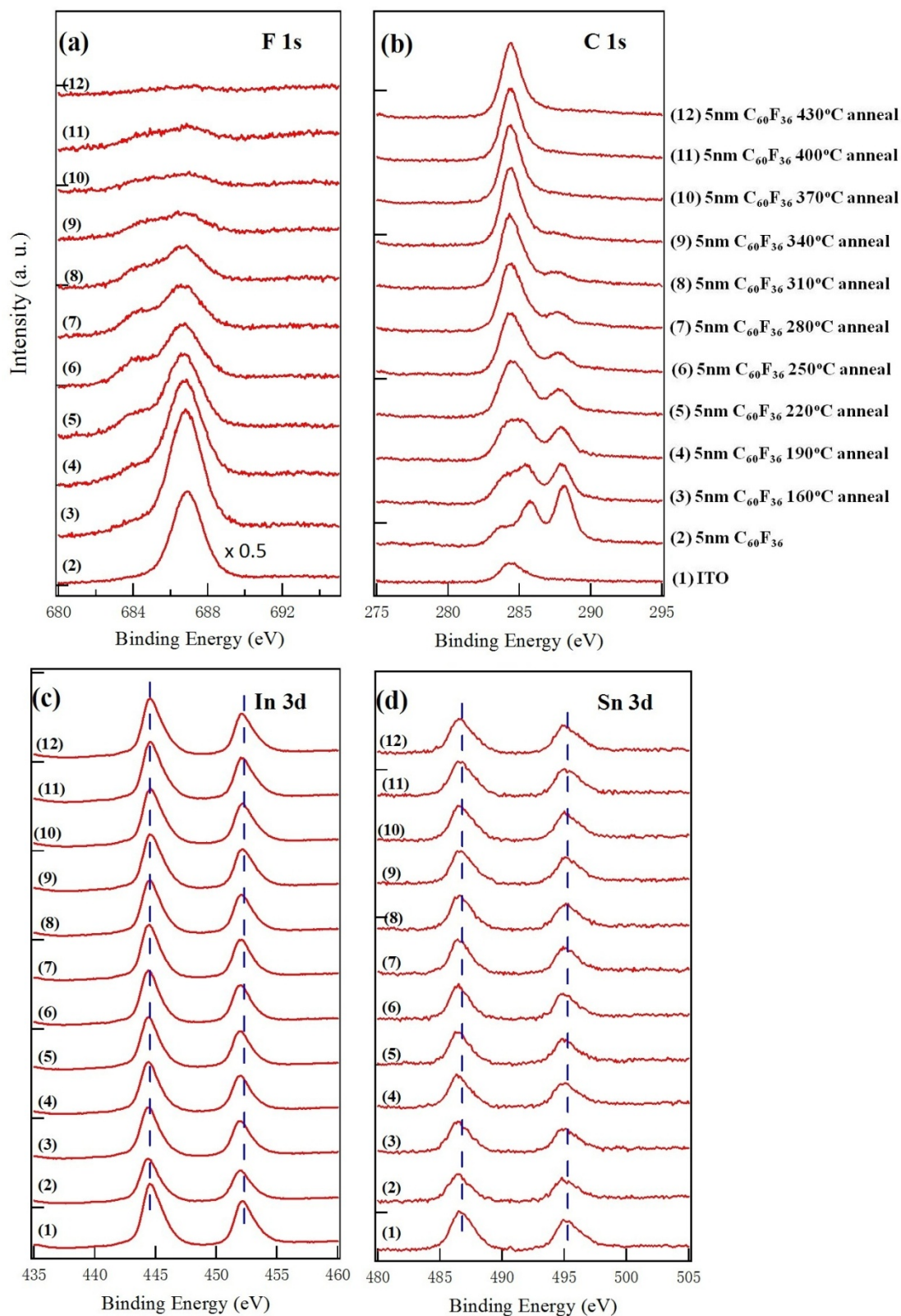


Figure S1. XPS spectra of (a) F 1s, (b) C 1s, (c) In 3d, and (d) Sn 3d core level evolution for 5.0 nm  $C_{60}F_{36}$  thin film on ITO with increasing anneal temperature.